

# US-Japan Seminar on Double-Beta Decay and Neutrino Mass



**Materials Purity:  
Ultra-Low-Background Copper,  
ICP-MS Assay,  
and Lead Surface Preparation  
for the Majorana Project**

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# Outline

- ▶ Motivation
- ▶ Electroformed Copper
- ▶ ICP-MS Copper Assay
- ▶ Lead Surface Preparation
- ▶ Summary



# Materials are Critical

- ▶ Depth is only part of the equation
- ▶ Must also have
  - Pure materials
  - Environmental gamma shielding
  - Environmental neutron shielding
  - Residual muon shielding
- ▶ Muon-induced secondary neutrons can dominate under good conditions

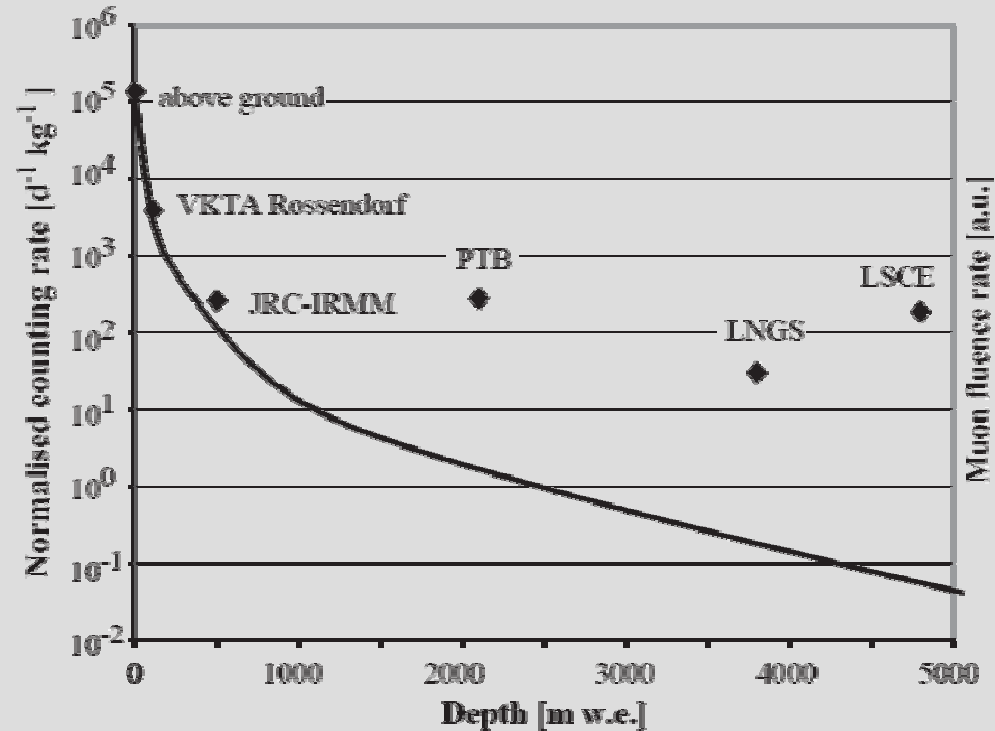


Fig. 1. The integral background counting rate from 40 to 2700 keV divided by the mass of the Ge-crystal for the best HPGe-detectors in some CELLAR laboratories. The solid line shows the muon fluence rate in arbitrary units normalised to the background counting rate above ground. All detectors have only passive shielding.

# Estimated backgrounds in the $0\nu\beta\beta$ -decay ROI



## Majorana Example

Background Source		Gross and Net Rates for Important Isotopes			Total Est. Background (per t-y)
		Counts in ROI per t-y			Counts in ROI
		$^{68}\text{Ge}$	$^{60}\text{Co}$		
Germanium (100 day exp)	Gross	2.54	1.22		
	Net	0.01	0.02		0.03
		$^{208}\text{Tl}$	$^{214}\text{Bi}$	$^{60}\text{Co}$	
Inner Mount	Gross	0.12	0.03	0.26	
	Net	0.01	0.00	0.00	0.01
Cryostat	Gross	0.77	0.16	0.58	
	Net	0.22	0.04	0.00	0.26
Copper Shield	Gross	2.28	0.30	0.02	
	Net	0.64	0.06	0.00	0.70
Small Parts	Gross	0.18	0.04	0.34	
	Net	0.02	0.01	0.00	0.03
External Sources (6000 mwe)		muons	cosmic activity	( $\alpha, n$ )	
Gross		0.03	1.33	0.003	
Net		0.003	0.18	0.003	0.18
$2\nu\beta\beta$ -decay					< 0.01
<b>TOTAL SUM</b>					<b>1.21</b>

Crystals are clean

Dominated by  $^{232}\text{Th}$  in Cu

See talk by T. Hossbach

Must go deep

- "Gross" indicates level of activity before any analysis cuts are applied.
- "Net" indicates level of activity after cuts have been applied.



# Copper Motivation

- ▶ Commercial high-purity copper is an attractive material for constructing ultra-low-background spectrometers.
- ▶ Thermal, mechanical, electrical, and vacuum properties enable vacuum cryostats, crystal mounts, heat conductors, electrical interconnects, etc.
- ▶ When even higher purity is required, additional electrolytic and chemical purification can be combined with the final fabrication step, resulting in “electroformed” copper parts of extreme purity.
- ▶ This process can be done underground, providing a potential way to eliminate cosmogenic activation products seen in copper with above-ground exposure.
- ▶ Additional purity improvements seem possible with modest additional chemistry.

# Ultra-Low-Background Electroformed Copper



Electroformed cups shown have wall thickness of only 250  $\mu\text{m}$ !

- ▶ Strength equal to OFHC
- ▶ Technology has small physical footprint for production
- ▶ Can be easily formed into thin, low-mass parts
- ▶ Purity established with IGEX\* experience, development continues

\*(International Germanium EXperiment)

# Low-Background Electroformed Copper Key Elements



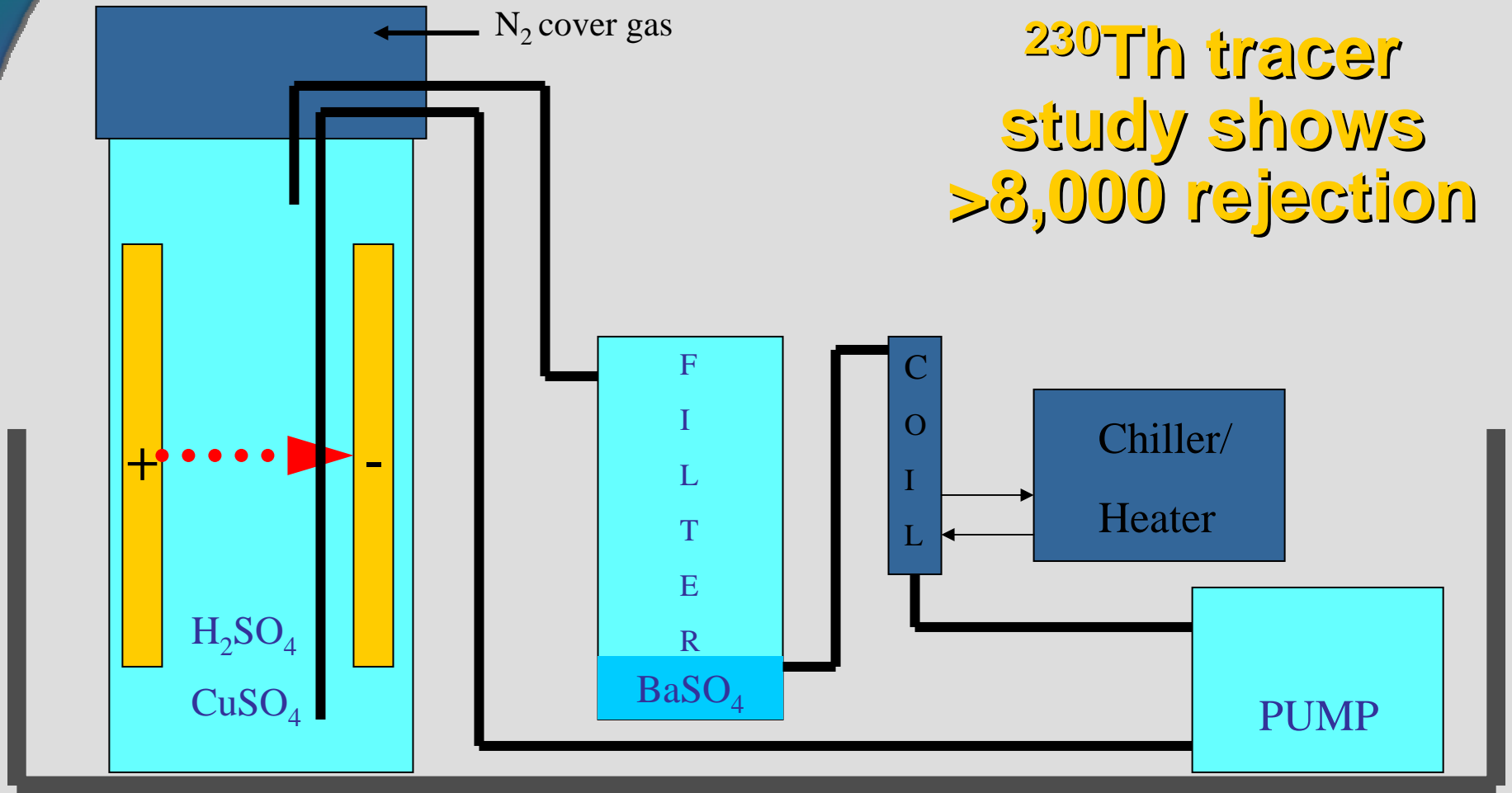
Low-background detector and  
electroformed cryostat during assembly

- ▶ Semiconductor-grade acids
- ▶ Glassware-free handling
- ▶ Copper sulfate purified by recrystallization
- ▶ Baths circulated with continuous microfiltration to remove oxides and precipitates
- ▶ Continuous barium scavenge removes radium
- ▶ Cover gas in plating tanks reduces oxide formation
- ▶ Periodic surface machining during production minimizes dendritic growth



# Electroforming Overview

**$^{230}\text{Th}$  tracer study shows >8,000 rejection**



Secondary Tank





# Plating Bath Process Parameters

- ▶ Plating is done onto polished, cleaned, stainless steel mandrels in the shape of the desired parts
- ▶ Current density is  $\sim 40$  mA/cm<sup>2</sup>
- ▶ Plating rate is  $\sim 0.05$  mm/h
- ▶ BaSO<sub>4</sub> collects in the micro-filtration stage and acts as radium scavenge
- ▶ CoSO<sub>4</sub> was added as a holdback carrier for the cosmogenic <sup>56,57,58,60</sup>Co present in the starting copper
- ▶ HCl and Thiourea affect copper crystal nucleation and grain size

Constituent	Concentration
CuSO <sub>4</sub>	188 g/l
H <sub>2</sub> SO <sub>4</sub>	75 g/l
HCl	30 mg/l
Thiourea	3 mg/l
CoSO <sub>4</sub>	1 mg/l
BaSO <sub>4</sub>	$\sim 1$ mg/l

# Chemistry & Cosmogenics



- ▶ Further improvements were made in the chemistry for electroformed Cu production
- ▶ U, Th progeny reduced substantially (100x, 10x) over early work [Bro95]
- ▶ Underground production would totally eliminate cosmogenic  $^{60}\text{Co}$ , other less-important cosmogenics
- ▶ Current chemistry development continues (tracer studies, mass balance, etc.)

~1995 to present  
 Electroformed copper radiochemistry gains:

- $\text{H}_2\text{SO}_4$  Purity
- Recrystallized  $\text{CuSO}_4$
- Barium scavenge

### Results:

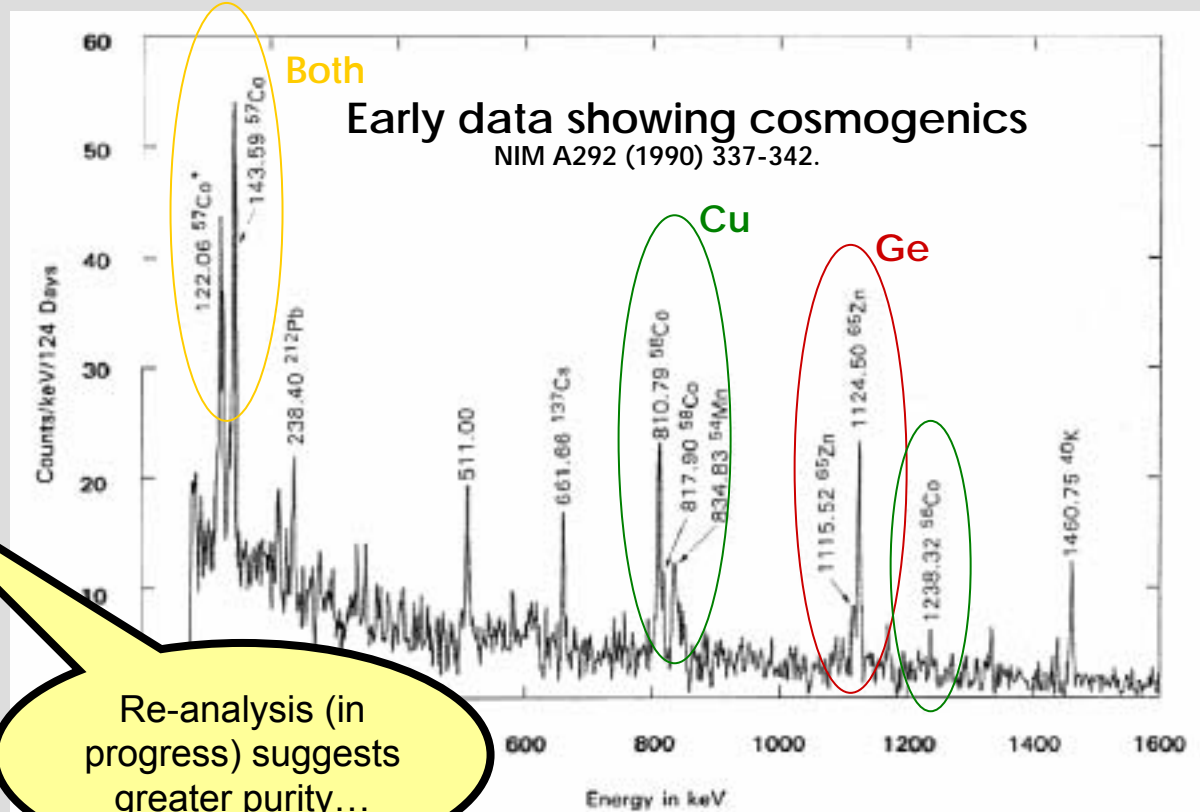
$^{226}\text{Ra}$  <25  $\mu\text{Bq/kg}$   
 $^{228}\text{Th}$  9  $\mu\text{Bq/kg}$

(Brodzinski et al, Journal of Radioanalytical and Nuclear Chemistry, 193 (1) 1995 pp. 61-70)

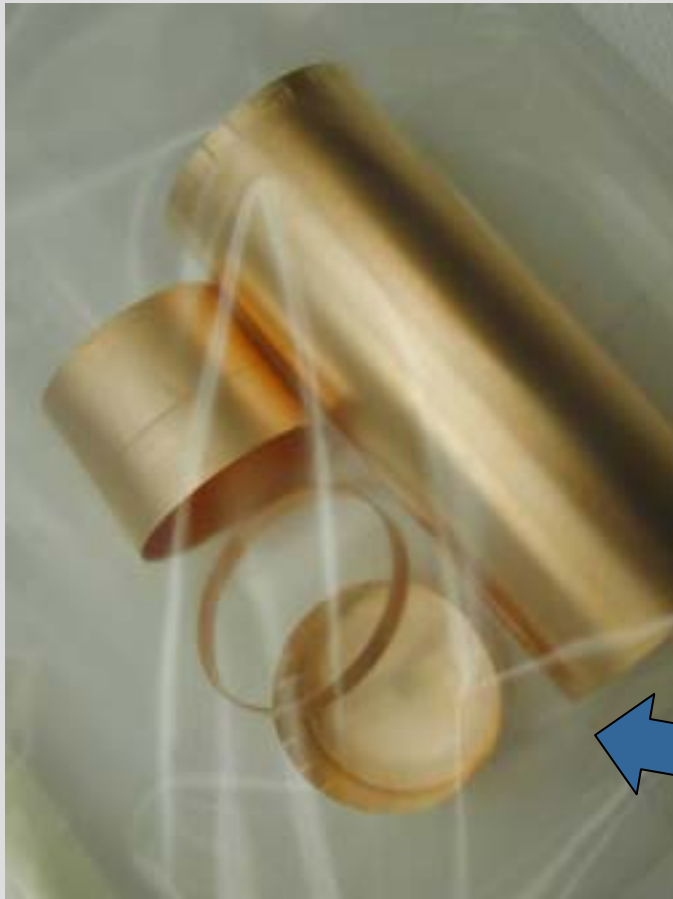
### LNGS NOSV High-Purity Cu:

$^{226}\text{Ra}$  <18  $\mu\text{Bq/kg}$   
 $^{228}\text{Th}$  <12  $\mu\text{Bq/kg}$

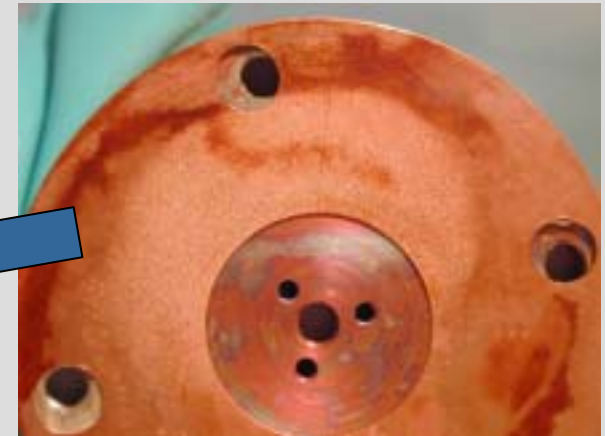
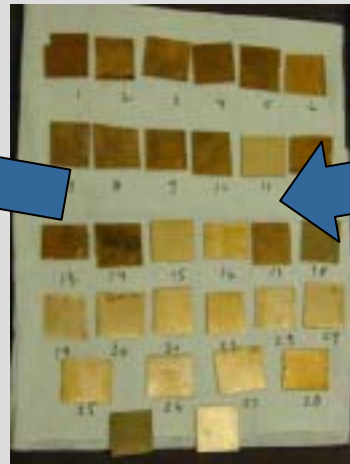
(M. Laubenstein et al, Applied Radiation and Isotopes, 61 (2004) 167-172)



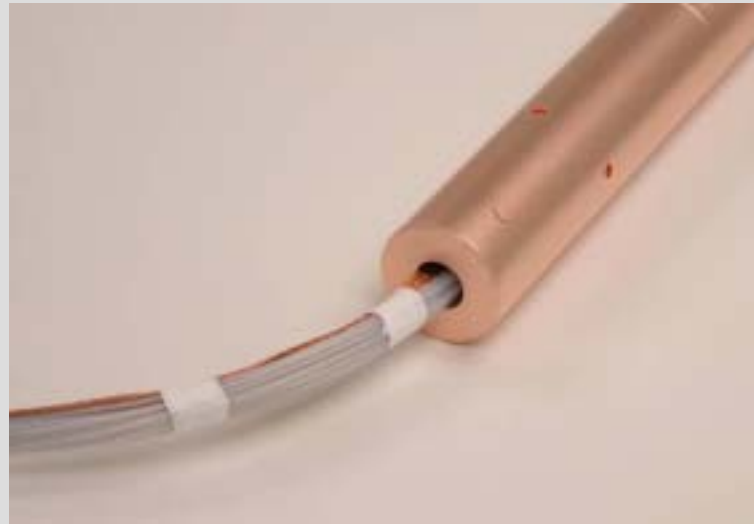
# Electroformed Copper Surface Cleaning & Passivation



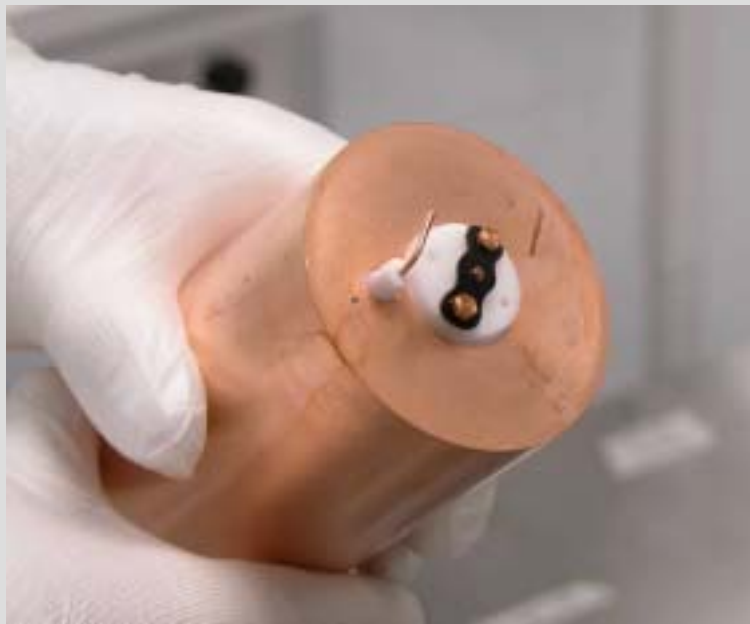
- ▶ Goal was to find copper cleaning process to replace destructive nitric acid etch
- ▶ Surface passivation was also desired
- ▶ Experiments inspired by CUORE conversations
- ▶ Tested several oxide removal methods
- ▶ Tested ~30 passivation chemistries
- ▶ H<sub>2</sub>O<sub>2</sub>-based cleaning & citric acid passivation were final result



# Examples from MEGA Detector



# Examples from MEGA Detector





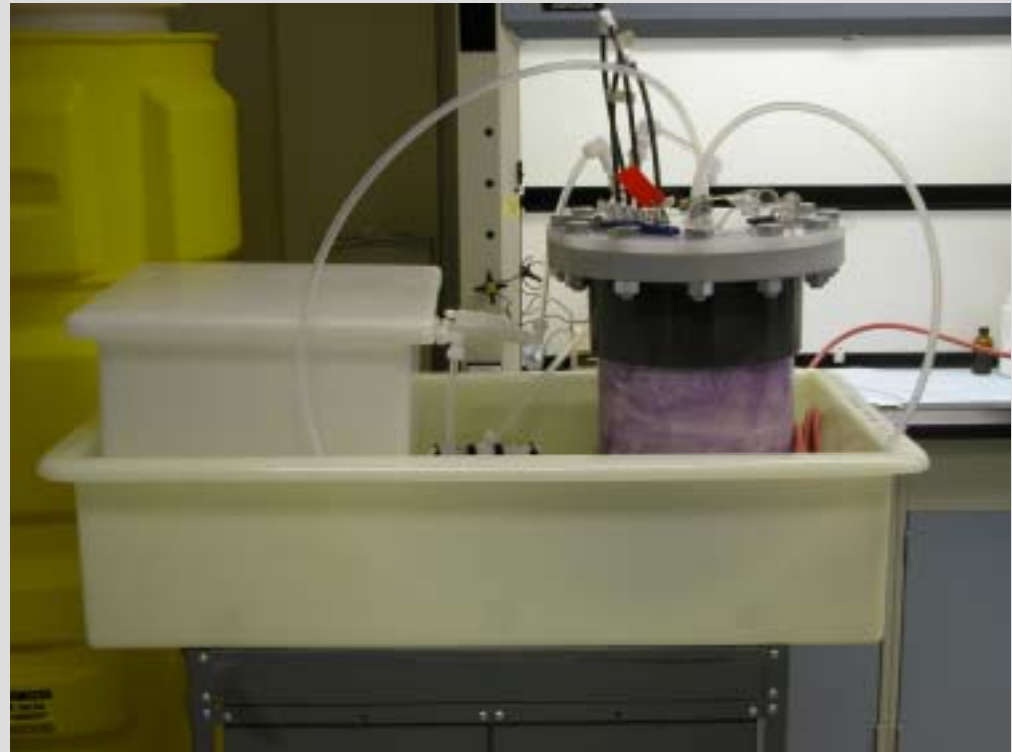
# Electroforming R&D is Ongoing



# LANL-PNNL Underground Cu Experiment



- ▶ Equipment underground at WIPP
- ▶ LANL, Majorana team will operate
- ▶ Will demonstrate cosmogenic suppression



# ICPMS Copper Purity Assay





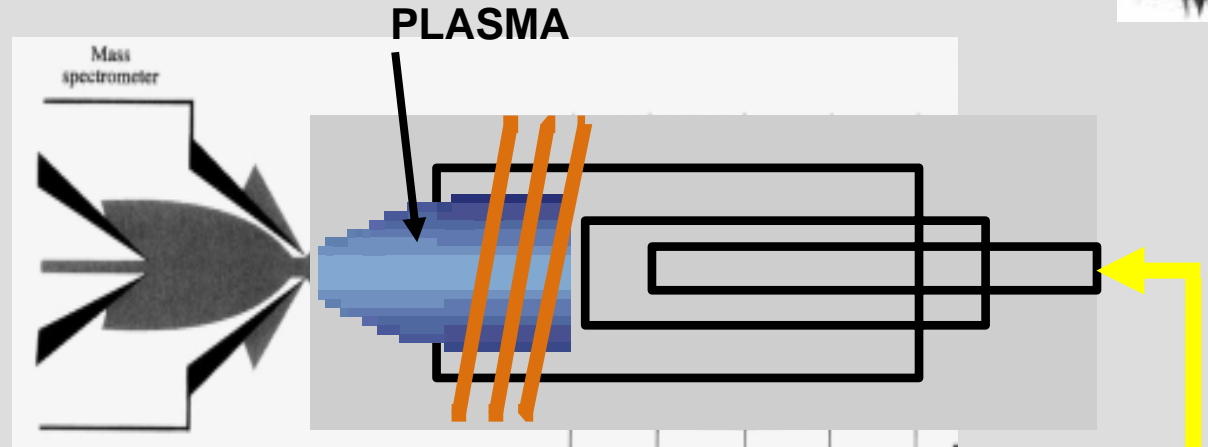
# Motivation

- ▶ Direct radiometric methods require large sample mass (~10 kg), long count time (~3 months), have reached limit
- ▶ Producing material for next-generation detector (Majorana) will require careful QA of even small parts
- ▶ Inductively-Coupled Plasma – Mass Spectrometry (ICP-MS) has good potential for reaching radiopurity goals

# Basic ICP/MS



mass spectrometer  
Quadrupole



ion detection

**EM**

FC

Daly

ASAT

sample & aerosols:

liquid

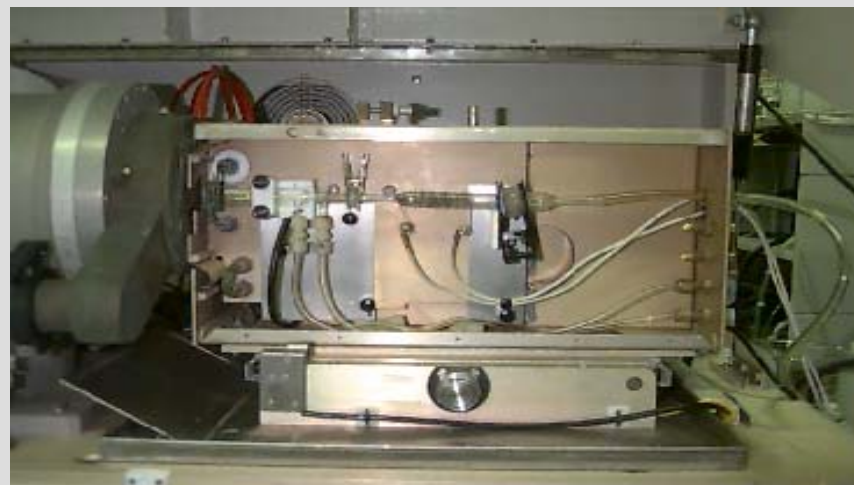
gases

solids

# PNNL ICP/MS Equipment

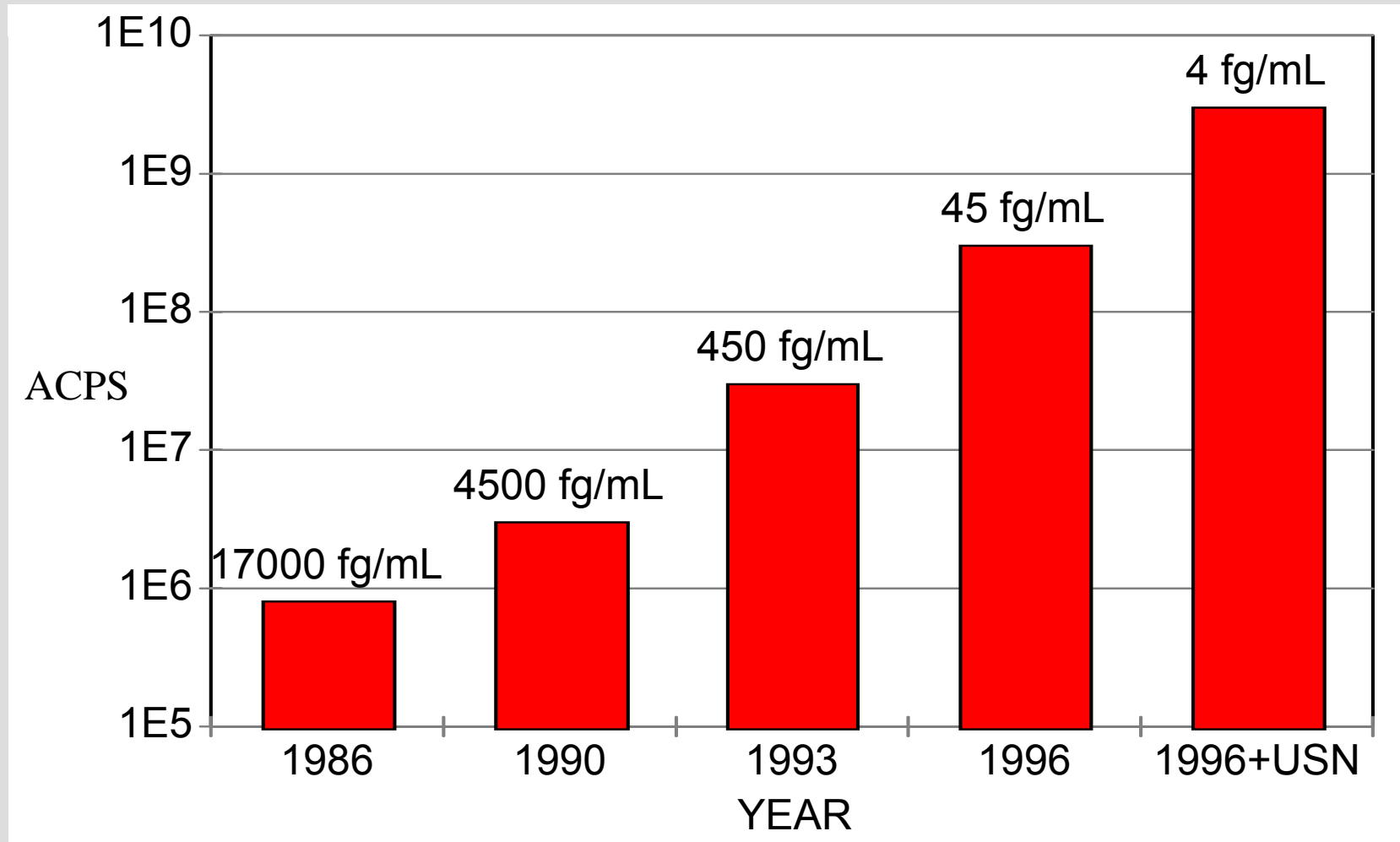


# Sample Introduction Methodologies





# DETECTION IMPROVEMENT IN ICP/MS



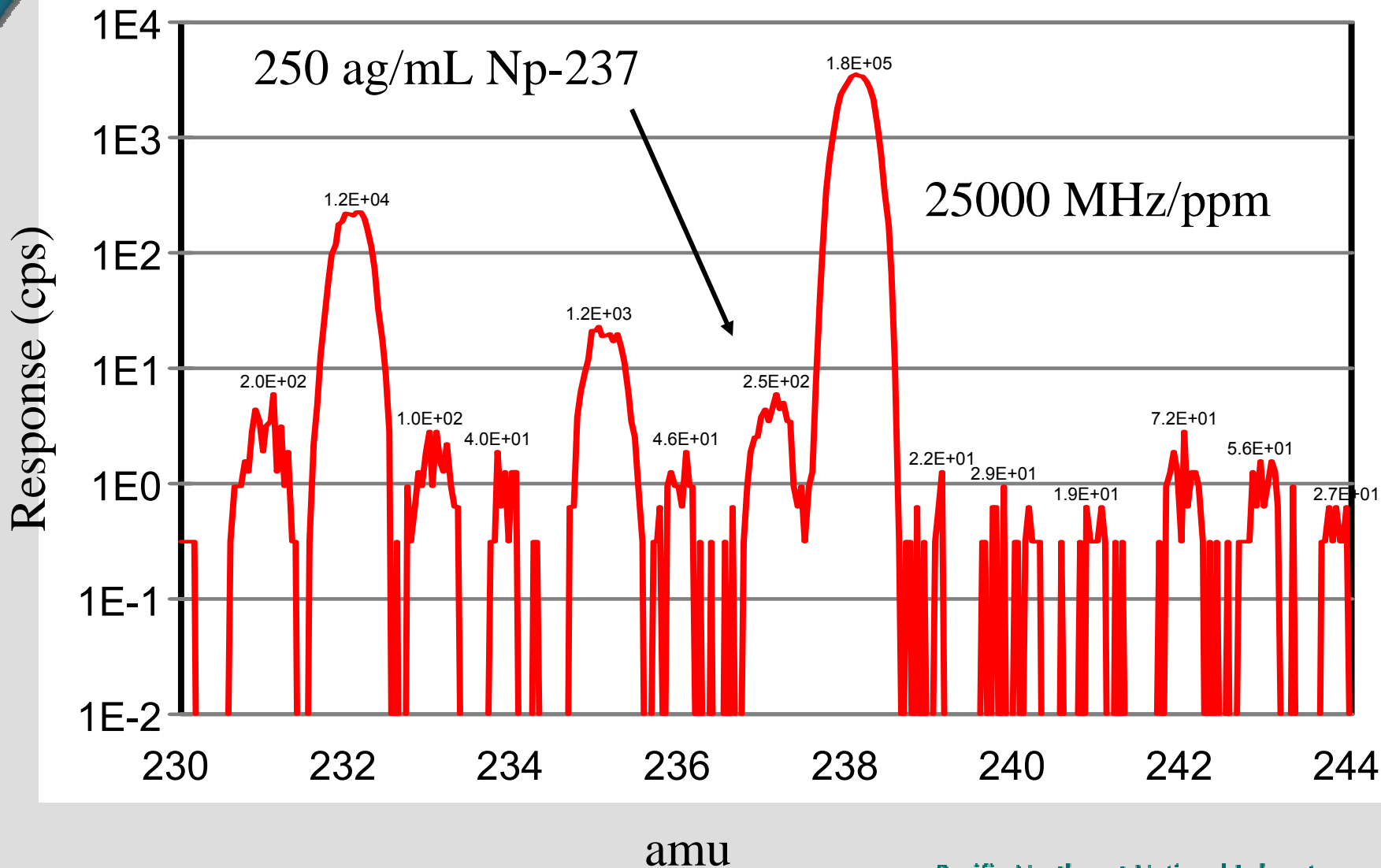
# ICP-MS DETECTION RANGES

Aqueous Standards



WEIGHT	PREFIX	$^{238}\text{U}$ ATOMS/ml	
$10^{-3}$ (ppt)	Milli	$2.53 \times 10^{18}$	<b>NORMAL ICP-MS RANGE</b>
$10^{-6}$ (ppm)	Micro	$2.53 \times 10^{15}$	
$10^{-9}$ (ppb)	Nano	$2.53 \times 10^{12}$	
$10^{-12}$ (ppt)	Pico	$2.53 \times 10^9$	
$10^{-15}$ (ppq)	Femto	$2.53 \times 10^6$	<b>THIS WORK</b>
$10^{-18}$ (pp?)	Atto	<b>2530</b>	
$10^{-21}$ (pp??)	Zepto	2.53	
$10^{-24}$ (pp???)	Guaca	0.00253	

# Direct Atto-gram/mL Detection





# Copper Sample Preparation

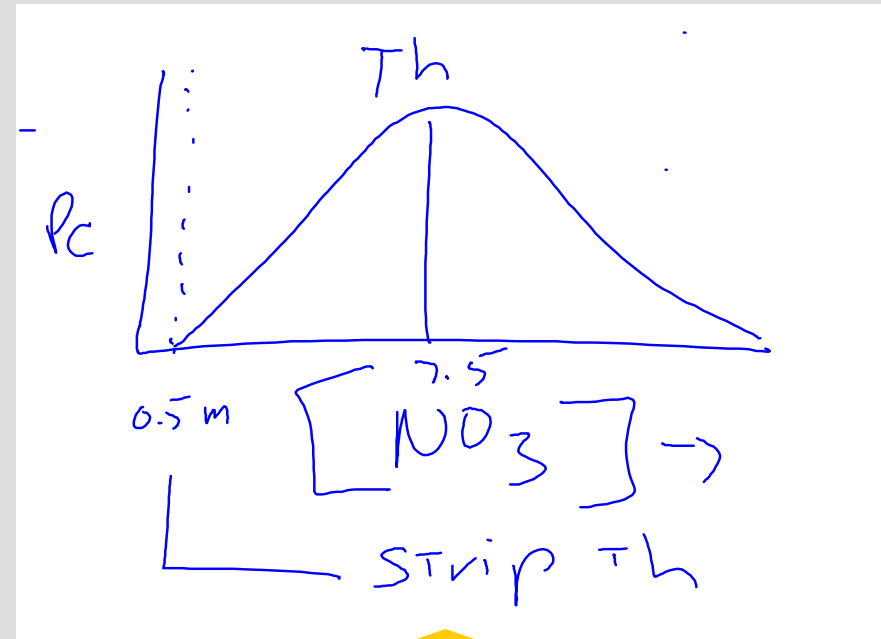
- ▶ Nominal 1g copper sample is placed in 75ml clear Teflon bottle
- ▶ 20ml 7.5M HNO<sub>3</sub> (<0.05pg/ml) is added
- ▶ Tracer (<sup>229</sup>Th or <sup>230</sup>Th) is added at about 10% of expected <sup>232</sup>Th value
- ▶ Gentle heat is applied until dissolution is complete
- ▶ Copper goes to +2 state





# Thorium Separation

- ▶ Column is 200-400 mesh anion resin
- ▶ Column is first washed with  $H_2O$
- ▶ Column is conditioned with 7.5M  $HNO_3$
- ▶ Sample is loaded (20 ml 7.5M  $HNO_3$ )
- ▶ Wash copper from column void volume (7.5M  $HNO_3$ )
- ▶ Elute (strip) thorium with 0.5M  $HNO_3$ 
  - Elute in 3 ml directly to MS



chemist explains to me  
how this works  
on my whiteboard...



# ICP-MS Instrument

- ▶ Condition instrument with 0.5M HNO<sub>3</sub> until stable background is achieved
- ▶ Switch in eluent (also 0.5M HNO<sub>3</sub>) and wait for signal to stabilize
- ▶ Measure (integrate) mass response during eluent ionization
  - Typically ~6 integration periods of 30 seconds each
  - Provides 10 seconds on each of three mass peaks (230.0, 230.5, 232.0) for each integration period



# Data Reduction

- ▶ Subtract instrument background from eluent signal
  - This is from 0.5M HNO<sub>3</sub> reagent and is small
- ▶ Subtract process blank from eluent signal
  - This is from an eluent blank prepared without copper and is larger
- ▶ Quote result (pg/g) based on tracer
- ▶ Convert to  $\mu\text{Bq/kg}$  equivalent  $^{232}\text{Th}$  (4x multiplier)



# First Copper Result

- ▶ Two 1-g samples of MEGA inner-can copper were analyzed
- ▶ Sample #1 (0.882 g)
  - The process blank was  $6.0 \pm 0.3$  pg/g
  - The sample yielded a value of
    - $7.3 \pm 0.7$  pg/g (gross)
    - or  $1.2 \pm 0.8$  pg/g (net)
  - This is a net  $^{232}\text{Th}$  activity of  $4.9 \pm 2.9$   $\mu\text{Bq/kg}$
- ▶ Sample #1 (0.936 g)
  - The process blank was  $5.7 \pm 0.3$  pg/g
  - The sample yielded a value of
    - $7.0 \pm 0.6$  pg/g (gross)
    - or  $1.3 \pm 0.7$  pg/g (net)
  - This is a net  $^{232}\text{Th}$  activity of  $5.2 \pm 2.8$   $\mu\text{Bq/kg}$

preliminary

# Cu ICP-MS Next Steps



## ▶ Sensitivity

- Preliminary result appears to be first positive indication of Th in Cu
- Anion column cleanup of 7.5M HNO<sub>3</sub> planned
- Sub-boiling distillation to further clean HNO<sub>3</sub> if necessary
- Instrument background now 6x lower

## ▶ Documentation

- Process will eventually transition into “service center” activity
- Will benefit from QA, standardized reporting

## ▶ Priority

- Repeat process blanks
- Repeat and extend copper measurements (starting stock, other Cu)
- Test reagent cleanup chemistry



# Pb Cleaning



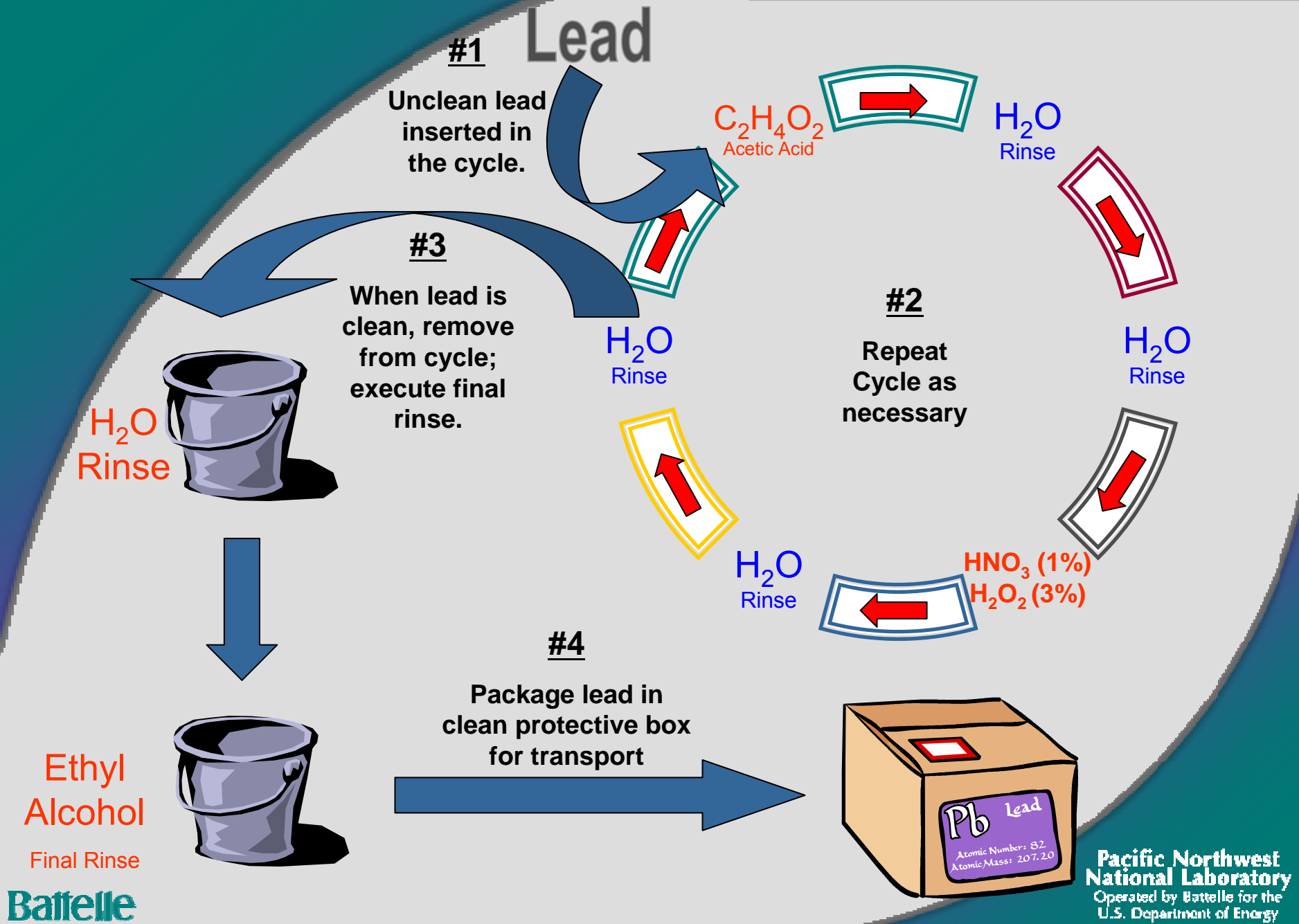
“Spanish” Lead~1542

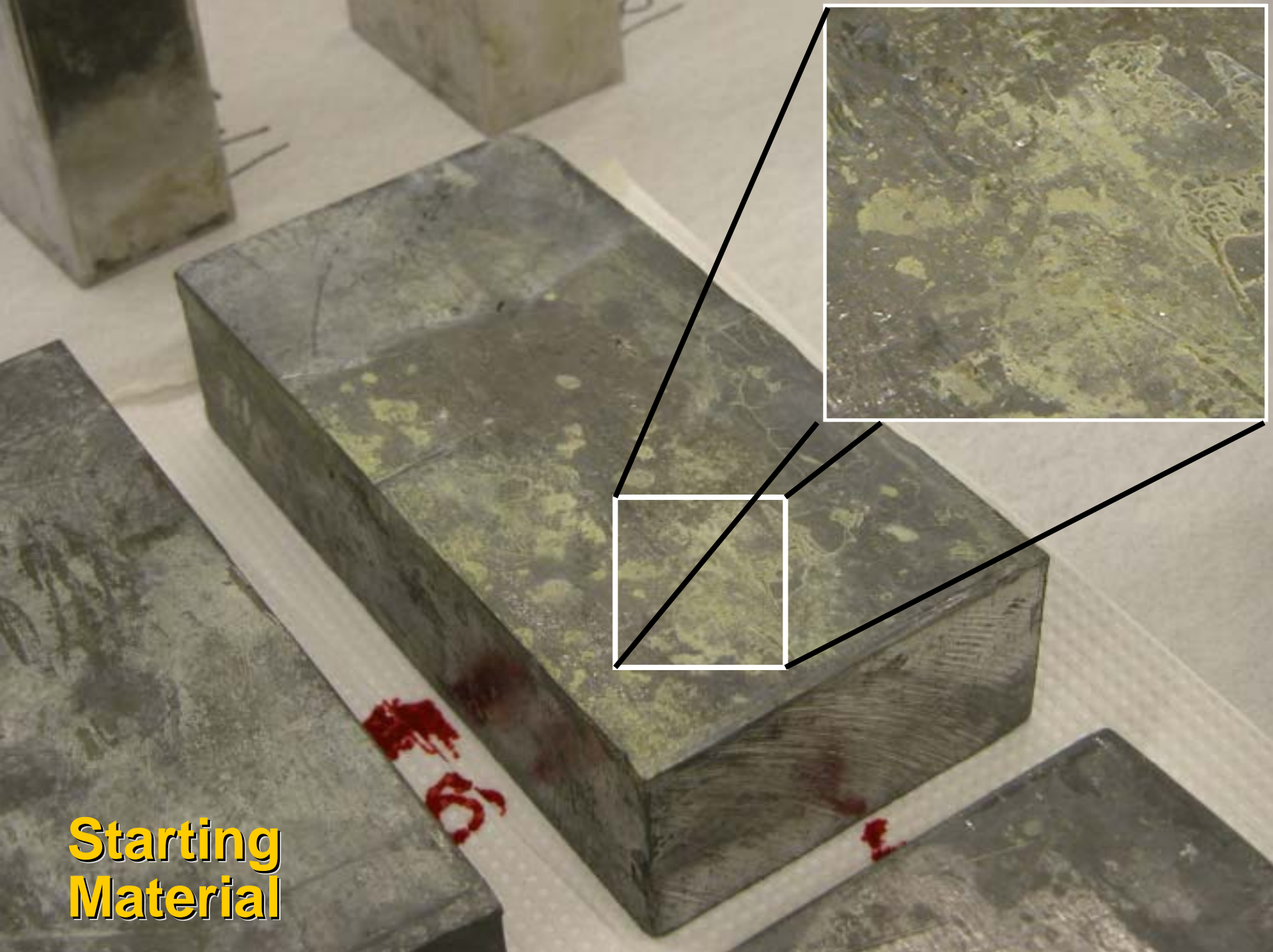
- ▶ Ancient lead is desired to avoid  $^{210}\text{Pb}$  backgrounds, present in all modern lead
- ▶ Materials are usually recovered needing extensive surface cleaning
- ▶ Even new lead may need oxide removal for safety reasons



“New” Lead ~1950 to ~1980

# Lead Brick Cleaning Process





**Starting  
Material**



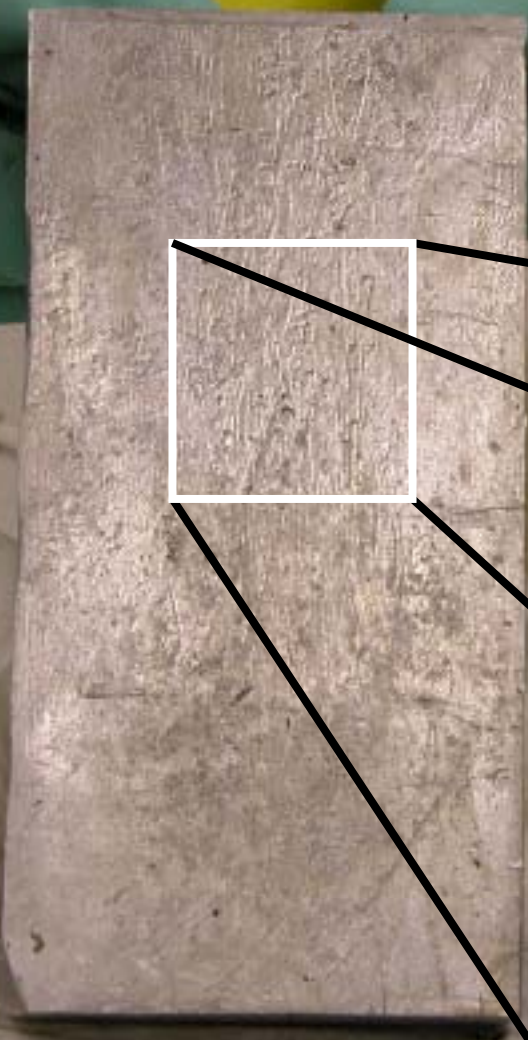
# Acetate Formation



# Acetate Removal



**Final  
Result**





# Summary

- ▶ Ultra-Low-Background Electroformed copper is an established technology, improvements continue
- ▶ R&D to reach Majorana assay targets underway
  - ICP-MS expected to reach Majorana target sensitivity for  $^{232}\text{Th}$  in copper
  - Surface  $\alpha$ ,  $\beta$  assay for Pb and Cu are planned
- ▶ Underground electroforming R&D in progress in two underground locations
  - Soudan (SBIR partner Jim Reeves)
  - WIPP (LANL Majorana team, Steve Elliott, et al.)
- ▶ Surface preparation chemistry being developed for lead



# Acknowledgements

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